

| L Number | Hits  | Search Text   | DB   | Time stamp          |
|----------|-------|---|--|---------------------|
| 1        | 1     | 6159643.pn.   | USPAT  | 2004/08/12<br>11:03 |
| 2        | 45    | Goldstein-Michael.in.   | USPAT;<br>US-PGPUB;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB<br>USPAT | 2004/08/12<br>11:04 |
| -        | 15760 | ((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)   | USPAT  | 2004/07/27<br>12:18 |
| -        | 1823  | ((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3))   | USPAT  | 2004/06/28<br>10:48 |
| -        | 97    | (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3)) and ((thermal adj expansion) or (titanium adj silicate)))  | USPAT  | 2004/06/28<br>12:12 |
| -        | 285   | (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3)) and isotropic\$3   | USPAT  | 2004/06/28<br>12:13 |
| -        | 272   | (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3)) and isotropic\$3 not (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3)) and ((thermal adj expansion) or (titanium adj silicate))))   | USPAT  | 2004/06/28<br>12:13 |
| -        | 243   | (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3)) and isotropic\$3 not (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3)) and ((thermal adj expansion) or (titanium adj silicate)))) and @ay<=2001   | USPAT  | 2004/06/28<br>12:46 |
| -        | 226   | (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3)) and isotropic\$3 not (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon) and (polish or polishing or cmp or planarize or planarization)) and (thermal adj anneal\$3)) and ((thermal adj expansion) or (titanium adj silicate)))) and @ay<=2001) and ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2) | USPAT  | 2004/06/28<br>12:47 |

|   |       |  |       |                     |
|---|-------|--|-------|---------------------|
| - | 28163 | ((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)  | USPAT | 2004/07/27<br>12:18 |
| - | 1499  | ((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (sacrificial with (oxide or dioxide or SiO or SiO?sub.2)))  | USPAT | 2004/07/27<br>12:24 |
| - | 264   | ((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (sacrificial with (oxide or dioxide or SiO or SiO?sub.2) same (isotropic\$3 or (wet adj etch\$3))))   | USPAT | 2004/07/27<br>13:46 |
| - | 264   | ((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (((sacrificial with (oxide or dioxide or SiO or SiO?sub.2) same (isotropic\$3 or (wet adj etch\$3))))   | USPAT | 2004/07/27<br>12:26 |
| - | 232   | (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (((sacrificial with (oxide or dioxide or SiO or SiO?sub.2) same (isotropic\$3 or (wet adj etch\$3)))) and @ay<=2001  | USPAT | 2004/07/27<br>12:26 |
| - | 185   | (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (((sacrificial with (oxide or dioxide or SiO or SiO?sub.2) same (isotropic\$3 or (wet adj etch\$3)))) and @ay<=2001) and (photo\$1lithograph\$3 or lithograph\$3)                    | USPAT | 2004/07/27<br>12:27 |
| - | 169   | (((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (((sacrificial with (oxide or dioxide or SiO or SiO?sub.2) same (isotropic\$3 or (wet adj etch\$3)))) and @ay<=2001) and (photo\$1lithograph\$3 or lithograph\$3)) and semiconductor | USPAT | 2004/07/27<br>13:24 |
| - | 7     | ("5171699"   "5194394"   "5340756"   "5387528"   "5404040"   "5656520"   "5668026").PN.  | USPAT | 2004/07/27<br>13:21 |
| - | 4259  | (CTE or (coefficient adj3 thermal adj expansion)) and (polish or polished or polishing or cmp or planarize or planarizing)   | USPAT | 2004/07/27<br>13:46 |

|   |      |   |       |                     |
|---|------|---|-------|---------------------|
| - | 4253 | ((CTE or (coefficient adj3 thermal adj expansion)) and (polish or polished or polishing or cmp or planarize or planarizing)) not ((((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (((sacrificial with (oxide or dioxide or SiO or SiO?sub.2)) same (isotropic\$3 or (wet adj etch\$3)))))) and @ay<=2001) and (photo\$1lithograph\$3 or lithograph\$3)) and semiconductor)  | USPAT | 2004/07/27<br>13:46 |
| - | 1499 | ((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (sacrificial with (oxide or dioxide or SiO or SiO?sub.2))  | USPAT | 2004/07/27<br>13:48 |
| - | 77   | ((CTE or (coefficient adj3 thermal adj expansion)) and (polish or polished or polishing or cmp or planarize or planarizing)) not ((((((crystall\$3 near3 silicon) or (poly\$1crystalline adj silicon) or polysilicon or TiSi or (titanium adj silicate) or ceramic) and (polish or polishing or cmp or planarize or planarization)) and (((sacrificial with (oxide or dioxide or SiO or SiO?sub.2)) same (isotropic\$3 or (wet adj etch\$3)))))) and @ay<=2001) and (photo\$1lithograph\$3 or lithograph\$3)) and semiconductor)) and (sacrificial with (oxide or dioxide or SiO or SiO?sub.2)) | USPAT | 2004/07/27<br>14:28 |
| - | 26   | (mirror with photo\$1lithograph\$3).clm.  | USPAT | 2004/07/27<br>15:30 |
| - | 425  | mirror with photo\$1lithograph\$3   | USPAT | 2004/07/27<br>15:30 |
| - | 3060 | (mirror or glass) with photo\$1lithograph\$3  | USPAT | 2004/07/27<br>15:30 |
| - | 507  | ((mirror or glass) with photo\$1lithograph\$3) and (polish or polishing or cmp or planarization or planarize or planarizing)  | USPAT | 2004/07/27<br>15:31 |
| - | 326  | ((mirror or glass) with photo\$1lithograph\$3) and (polish or polishing or cmp or planarization or planarize or planarizing)) and (sacrificial or (silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)   | USPAT | 2004/07/27<br>15:32 |
| - | 307  | ((mirror or glass) with photo\$1lithograph\$3) and (polish or polishing or cmp or planarization or planarize or planarizing)) and (sacrificial or (silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and @ay<=2001  | USPAT | 2004/07/27<br>15:33 |
| - | 213  | ((mirror or glass) with photo\$1lithograph\$3) and (polish or polishing or cmp or planarization or planarize or planarizing)) and (sacrificial or (silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and @ay<=2001) and (crystal or crytalline or poly\$1silicon or poly\$1crystalline)   | USPAT | 2004/07/27<br>15:37 |

|   |      |   |       |                     |
|---|------|---|-------|---------------------|
| - | 174  | ((((mirror or glass) with photo\$1lithograph\$3) and (polish or polishing or cmp or planarization or planarize or planarizing)) and (sacrificial or (silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)) and @ay<=2001) and (crystal or crytalline or poly\$1silicon or poly\$1crystalline)) and semiconductor  | USPAT | 2004/07/27<br>15:37 |
| - | 5187 | ((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor  | USPAT | 2004/08/10<br>16:46 |
| - | 4348 | ((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor  | USPAT | 2004/08/10<br>10:43 |
| - | 1443 | ((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and (polish or polishing or polished or planarize\$1 or planarizing or cmp)   | USPAT | 2004/08/10<br>15:54 |
| - | 314  | ((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and (polish or polishing or polished or planarize\$1 or planarizing or cmp)) and ((silicon adj dioxide) or (silicon adj oxide) or SiO or SiO?sub.2) with (thermal or grow or growing))  | USPAT | 2004/08/10<br>10:45 |
| - | 289  | ((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and (polish or polishing or polished or planarize\$1 or planarizing or cmp)) and ((silicon adj dioxide) or (silicon adj oxide) or SiO or SiO?sub.2) with (thermal or grow or growing)) and @ay<=2001  | USPAT | 2004/08/10<br>10:45 |
| - | 270  | ((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and (polish or polishing or polished or planarize\$1 or planarizing or cmp)) and ((silicon adj dioxide) or (silicon adj oxide) or SiO or SiO?sub.2) with (thermal or grow or growing)) and @ay<=2001) and (etch or etching)   | USPAT | 2004/08/10<br>10:48 |
| - | 203  | ((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and ((polish or polishing or polished or planarize\$1 or planarizing or cmp) with (crystalline or poly\$1silicon))  | USPAT | 2004/08/10<br>15:55 |
| - | 157  | ((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and ((polish or polishing or polished or planarize\$1 or planarizing or cmp) with (crystalline or poly\$1silicon))) not (((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and (polish or polishing or polished or planarize\$1 or planarizing or cmp)) and ((silicon adj dioxide) or (silicon adj oxide) or SiO or SiO?sub.2) with (thermal or grow or growing)) and @ay<=2001) and (etch or etching)) | USPAT | 2004/08/10<br>15:55 |

|   |      |  |       |                     |
|---|------|--|-------|---------------------|
| - | 141  | (((((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and ((polish or polishing or polished or planarize\$1 or planarizing or cmp) with (crystalline or poly\$1silicon))) not ((((((titanium adj silicate) or TiSi or TiSiO or ceramic) and (crystalline adj (Si or silicon) or poly\$1silicon)) and semiconductor) and (polish or polishing or polished or planarize\$1 or planarizing or cmp)) and (((silicon adj dioxide) or (silicon adj oxide) or SiO or SiO?sub.2) with (thermal or grow or growing))) and @ay<=2001) and (etch or etching))) and @ay<=2001 | USPAT | 2004/08/10<br>15:55 |
| - | 623  | titanium adj silicate  | USPAT | 2004/08/10<br>16:46 |
| - | 43   | (titanium adj silicate) and (polish or polishing or cmp or planarize or planarizing)   | USPAT | 2004/08/10<br>17:34 |
| - | 5    | ("5272744"   "5978441"   "6048652"   "6159643"   "6159824").PN.  | USPAT | 2004/08/10<br>16:49 |
| - | 44   | ULE and (polish or polishing or cmp or planarize or planarizing)   | USPAT | 2004/08/10<br>17:34 |
| - | 17   | (ULE and (polish or polishing or cmp or planarize or planarizing)) and (crystal or crystalline or poly\$1silicon)  | USPAT | 2004/08/10<br>17:34 |
| - | 7    | ("2326059"   "5154744"   "5506080"   "5510230"   "6048652"   "6159643"   "6178221").PN.  | USPAT | 2004/08/10<br>17:39 |
| - | 5879 | (ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)   | USPAT | 2004/08/11<br>12:03 |
| - | 1315 | ((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si)) or polysilicon)   | USPAT | 2004/08/11<br>12:04 |
| - | 1227 | ((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si)) or polysilicon)) and @ay<=2001  | USPAT | 2004/08/11<br>10:44 |
| - | 646  | ((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si)) or polysilicon)) and @ay<=2001) and (lithography or lithographic or photo\$1lithograph\$2)  | USPAT | 2004/08/11<br>10:44 |
| - | 501  | (((((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si)) or polysilicon)) and @ay<=2001) and (lithography or lithographic or photo\$1lithograph\$2)) and ((silicon adj oxide) or (silicon adj dioxide) or siO or SiO?sub.2)   | USPAT | 2004/08/11<br>12:03 |
| - | 187  | (((((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si)) or polysilicon)) and @ay<=2001) and (lithography or lithographic or photo\$1lithograph\$2)) and (((silicon adj oxide) or (silicon adj dioxide) or siO or SiO?sub.2) with (thermal or anneal or annealling))  | USPAT | 2004/08/11<br>11:34 |

|   |      |   |                       |                     |
|---|------|---|-----------------------|---------------------|
| - | 19   | ("4846931"   "4883561"   "5073230"   "5122852"   "5201996"   "5286335"   "5344517"   "5391257"   "5641381"   "5764820"   "5985742"   "6010579"   "6120597"   "6159323"   "6159824"   "6159825"   "6162705"   "6204151"   "6303468").PN.   | USPAT                 | 2004/08/11<br>11:11 |
| - | 7    | ("2326059"   "5154744"   "5506080"   "5510230"   "6048652"   "6159643"   "6178221").PN.   | USPAT                 | 2004/08/11<br>11:12 |
| - | 314  | (((((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si) or polysilicon)) and @ay<=2001) and (lithography or lithographic or photo\$1lithograph\$2)) and ((silicon adj oxide) or (silicon adj dioxide) or siO or SiO?sub.2)) not (((((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si) or polysilicon)) and @ay<=2001) and (lithography or lithographic or photo\$1lithograph\$2)) and ((silicon adj oxide) or (silicon adj dioxide) or siO or SiO?sub.2)) with (thermal or anneal or annealling)))                        | USPAT                 | 2004/08/11<br>11:34 |
| - | 114  | (((((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si) or polysilicon)) and @ay<=2001) and (lithography or lithographic or photo\$1lithograph\$2)) and ((silicon adj oxide) or (silicon adj dioxide) or siO or SiO?sub.2)) not (((((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and (((crystalline or crystal) near3 (silicon or si) or polysilicon)) and @ay<=2001) and (lithography or lithographic or photo\$1lithograph\$2)) and ((silicon adj oxide) or (silicon adj dioxide) or siO or SiO?sub.2)) with (thermal or anneal or annealling))) and (molybdenum or Mo) | USPAT                 | 2004/08/11<br>11:34 |
| - | 2725 | (ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)  | US-PGPUB;<br>EPO; JPO | 2004/08/11<br>12:03 |
| - | 1107 | ((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and @ay<=2001  | US-PGPUB;<br>EPO; JPO | 2004/08/11<br>12:03 |
| - | 484  | ((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and @ay<=2001) and ((silicon adj oxide) or (silicon adj dioxide) or siO or SiO?sub.2)  | US-PGPUB;<br>EPO; JPO | 2004/08/11<br>12:04 |
| - | 164  | (((((ULE or (thermal adj expansion) or CTE! or zerodur) and (polish or polishing or cmp or planarize or planarizing)) and @ay<=2001) and ((silicon adj oxide) or (silicon adj dioxide) or siO or SiO?sub.2)) and (((crystalline or crystal) near3 (silicon or si) or polysilicon))  | US-PGPUB;<br>EPO; JPO | 2004/08/11<br>14:05 |

|   |     |   |       |                     |
|---|-----|---|-------|---------------------|
| - | 5   | ((("5272744") or ("5978441") or ("6048652") or ("6159643") or ("6159824")).PN.  | USPAT | 2004/08/11<br>15:00 |
| - | 1   | ("6613862").PN.   | USPAT | 2004/08/11<br>15:00 |
| - | 1   | ("6613682").PN.   | USPAT | 2004/08/11<br>15:34 |
| - | 12  | ("4713141"   "4948462"   "5372673"   "5436205"   "5492597"   "5565681"   "5605601"   "5668038"   "5753533"   "5759920"   "5779926"   "5866483").PN.                 | USPAT | 2004/08/11<br>15:01 |
| - | 711 | mask near blank   | USPAT | 2004/08/11<br>15:34 |
| - | 11  | (mask near blank) and ULE   | USPAT | 2004/08/11<br>15:36 |
| - | 117 | (mask near blank) and (polish or polishing or cmp or planarize or planarization or planarizing)   | USPAT | 2004/08/11<br>15:46 |
| - | 112 | ((mask near blank) and (polish or polishing or cmp or planarize or planarization or planarizing)) not ((mask near blank) and ULE)                                   | USPAT | 2004/08/11<br>15:37 |
| - | 102 | ((mask near blank) and (polish or polishing or cmp or planarize or planarization or planarizing)) not ((mask near blank) and ULE)) and @ay<=2001                    | USPAT | 2004/08/11<br>15:37 |
| - | 23  | mask and (polish or polishing or cmp or planarize or planarization or planarizing) and (ULE or (ultra adj low adj expansion))                                       | USPAT | 2004/08/11<br>16:16 |
| - | 5   | ("5272744"   "5978441"   "6048652"   "6159643"   "6159824").PN.   | USPAT | 2004/08/11<br>15:50 |
| - | 11  | ULE with (polish or polishing or cmp or polished or planarize or planarizing)   | USPAT | 2004/08/11<br>16:19 |
| - | 6   | (ULE same (polish or polishing or cmp or polished or planarize or planarizing)) not (ULE with (polish or polishing or cmp or polished or planarize or planarizing)) | USPAT | 2004/08/11<br>16:19 |
| - | 17  | ULE same (polish or polishing or cmp or polished or planarize or planarizing)   | USPAT | 2004/08/11<br>16:20 |